

REMARKS

By this amendment, claims 1 and 35-38 are amended. Accordingly, claims 1-38 are currently pending in the application, of which claims 1, 10 and 35 are independent claims. Claims 10-34 have been previously allowed.

In view of the above amendments and the following Remarks, Applicant respectfully requests reconsideration and timely withdrawal of the pending rejections for the reasons discussed below.

Examiner Interview

Applicant appreciates that the Examiner granted an interview on March 9, 2004. During the interview, the Examiner expressed that the limitation “formed of the same layer” appears to be a process limitation and hence inappropriate for the structural claims. To address this issue, in the response, the claims have been amended to recite the invention with structural limitations.

Rejections Under 35 U.S.C. §112, second paragraph

Claims 1-9 and 35-38 stand rejected under 35 U.S.C. §112, second paragraph as being indefinite. Applicants respectfully traverse this rejection for at least the following reasons.

With respect to the antecedent basis issues, independent claims 1 and 35 have been amended to delete the recitations of “the same layer”.

In the Office Action, the Examiner stated “It is unclear how, in the liquid crystal display device, the light interception pattern (or the light interceptor) and the semiconductor pattern (or the semiconductor layer) have the same layer. Although they are formed of the same layer during

manufacturing process, the light interception pattern and the semiconductor pattern are two separate patterns in the device” (Office Action, page 2).

In this response, claim 1 has been amended to delete “a light interception pattern formed of the same layer as the semiconductor pattern” and to read “*a semiconductor layer comprising a semiconductor pattern and a light interception pattern; ... a thin film transistor ... including the semiconductor pattern*”.

Similarly, independent claim 35 has been amended to delete “a light interceptor made of the same layer as the semiconductor layer and overlapping the gap” and to read “*a semiconductor layer comprising a semiconductor pattern and a light interception pattern; ... said thin film transistor including the semiconductor pattern; and ... wherein the light interception pattern overlaps the gap*” .

Applicant believes that the amendments made to claims 1 and 35 are consistent with the Examiner’s understanding “Although they are formed of the same layer during manufacturing process, the light interception pattern and the semiconductor pattern are two separate patterns in the device” (Office Action, page 2) without causing any indefiniteness issues.

Accordingly, Applicant respectfully requests withdrawal of the 35 U.S.C. §112, second paragraph rejection of claims 1-9 and 35-38.

Rejections Under 35 U.S.C. §102

Claims 1-9 and 35-38 stand rejected under 35 U.S.C. §102(e) as being anticipated by U. S. Patent No. 6,466,289 issued to Lee, *et al.* (“Lee”). Applicants respectfully traverses this rejection for at least the following reasons.

Amended independent claim 1 recites “a semiconductor layer comprising a semiconductor pattern and a light interception pattern”. Amended independent claim 35 recites “a semiconductor layer comprising a semiconductor pattern and a light interception pattern”.

In the Office Action, the Examiner stated “a light interception pattern 64 of a first data line 60 formed of the same layer as the semiconductor pattern ...”. However, the two light-shield strips 64 are portions of the first data line 60. This means the two light-shield strips 64 and channel layer 40 (i.e., semiconductor layer) in Fig. 3 are formed from two different layers, respectively.

Lee fails to disclose or suggest “*a semiconductor layer comprising a semiconductor pattern and a light interception pattern*”, as recited in claim 1, and “*a semiconductor layer comprising a semiconductor pattern and a light interception pattern*”, as recited in claim 35. Thus, it is submitted that claims 1 and 35 are patentable over Lee. Claims 2-9 and 36-38 that are dependent from claims 1 and 35 would be also patentable at least for the same reason. Accordingly, Applicant respectfully requests withdrawal of the 35 U.S.C. §102(e) rejection of claims 1-9 and 35-38.

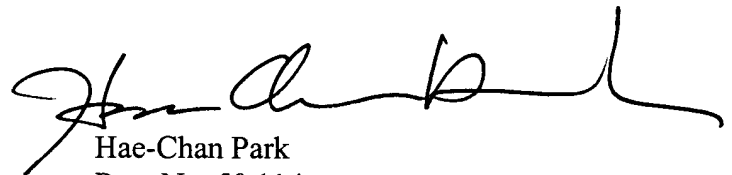
CONCLUSION

Applicant believes that a full and complete response has been made to the pending Office Action and respectfully submit that all of the stated grounds for rejection have been overcome or rendered moot. Accordingly, Applicant respectfully submits that all pending claims are allowable and that the application is in condition for allowance.

Should the Examiner feel that there are any issues outstanding after consideration of this response, the Examiner is invited to contact the Applicant's undersigned representative at the number below to expedite prosecution.

Prompt and favorable consideration of this Reply is respectfully requested.

Respectfully submitted,



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